

Notice of References Cited

Application/Control No.

10/092,308

Applicant(s)/Patent Under
Reexamination
ENDO, HIROSHI

Examiner

Thao X Le

Art Unit

2814

Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,455,364	09-2002	Asai et al.	438/235
*	B	US-6,392,278	05-2002	Kimura, Shingo	257/401
	C	US-6,204,133	03-2001	Yu et al.	438/299
	D	US-6,506,649	01-2003	Fung et al.	438/300
	E	US-5,693,544	12-1997	Abrokwah et al.	438/285
	F	US-5,550,065	08-1996	Hashemi et al.	438/182
	G	US-6,037,245	03-2000	Matsuda, Hajime	438/586
	H	US-5,334,542	08-1994	Saito et al.	438/579
	I	US-5,621,233	04-1997	Sharma et al.	257/316
	J	US-6,239,007	05-2001	Wu, Chi-Hsi	438/585
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Silicon Processing for VLSI Era, Volume 1 - Process Technology by S. Wolf and R.N. Tauber, pages 407-409
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.